

# Epitaxial Microstructures; Academic Press, 1994; 1994; 426 pages; 9780080864372

The epitaxial films grow upward and consume the amorphous regions. The crystallization temperature of both LaAlO<sub>3</sub> and MgAl<sub>2</sub>O<sub>4</sub> are lower for thin films than for bulk samples due to the substrate seeding. The transformation of LaAlO<sub>3</sub> is not linear growth as in typical homoepitaxy. Some of the recent volumes, such as Hydrogen in Semiconductors, Imperfections in III/V Materials, Epitaxial Microstructures, High-Speed Heterostructure Devices, Oxygen in Silicon, and others promise that this tradition will be maintained and even expanded. Professor Weber, a well-known expert in the field of semiconductor materials, will further contribute to continuing the series' tradition of publishing timely, highly relevant, and long-impacting volumes. Growing of epitaxial Fe<sub>50</sub>Mn<sub>50</sub>/Fe/Mo/R-sapphire films was performed with a new configuration of two in-plane easy axes of Fe(001)-layer magnetization in which application of annealing in a magnetic field forms an unidirectional anisotropy. The microstructures made from these films exhibited an exchange bias  $\approx 35$  G along an exchange field generated at antiferromagnet/ferromagnet (AFM/FM) interface.